			DB	Time stamp
L	Hits	Search Text	פע	Time Stamp
Number				2002 (02 (10
-	215	polysilicon same (pores asperit\$3)	USPAT	2003/03/19
				11:07
-	5677	mask near3 alignment	USPAT	2003/03/19
				11:06
_	3996	(mask near3 alignment) and etch\$3	USPAT	2003/03/19
				10:34
l _	479	(mask near3 alignment) and etch\$3 near2	USPAT	2003/03/19
		(poly polysilicon)		11:07
_	56		USPAT	2003/03/19
		(poly polysilicon)) and mark\$1		11:06
_	4522	mask near3 alignment	US-PGPUB;	2003/03/19
-	4322	mask fleats allymment	EPO; JPO;	11:07
			DERWENT	
	•	(mask near3 alignment) and mark\$1 and	USPAT	2003/03/19
-	0	(mask nears alignment) and marks and	USPAI	11:07
	_	etch\$3 near2 (poly polysilicon)	HC DCDHD.	2003/03/19
-	9	(mask near3 alignment) and mark\$1 and	US-PGPUB; EPO; JPO;	11:07
		etch\$3 near2 (poly polysilicon)		11:07
			DERWENT	0000 (00 (10
-	2485	438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
1				11:08
-	342	438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
		and ion near implantat\$3		11:10
-	338	(438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
		and ion near implantat\$3) and etch\$3	•	11:10
-	7666	430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19
				11:09
-	414	216/47.ccls.	USPAT	2003/03/19
İ				11:10
l _	7940	430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19
1		216/47.ccls.		11:10
	454		USPAT	2003/03/19
		216/47.ccls.) and ion near implantat\$3		11:10
_	435		USPAT	2003/03/19
	133	216/47.ccls.) and ion near implantat\$3)		11:10
		and etch\$3		
	419		USPAT	2003/03/19
i -	419	216/47.ccls.) and ion near implantat\$3)	ODIAL	11:15
				11.13
1		and etch\$3) not		
		((438/703,704,706,712,719,720,723,724.ccls	•	
	_	and ion near implantat\$3) and etch\$3)	IICDAT	2003/03/19
-	1	("6200903").PN.	USPAT	11:15
	_			
-	5	("4068018" "4253888" "4321317"	USPAT	2003/03/19
		"5009720" "6001739").PN.	<u> </u>	11:15